

Notice of References Cited	Application/Control No. 09/846,697	Applicant(s)/Patent Under Reexamination FERM ET AL.	
	Examiner John A. McPherson	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Resists in Microlithography", O'Brien et al., pages 325 to 376 of Microelectronics Processing: Chemical Engineering Aspects, American Chemical Society, 1989.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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